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Characterization of a commercial plasma source for plasma etching of substrates[1] DERETH DRAKE, Valdosta State University, BAKARI BETHEA, BB Intuitive Tutoring Company, ARTHUR BUI, Centauri, LLC, ERIC BURNS, ZACHARY BARTON, GABRIELLA MILES, ASHLEY RAULERSON, Valdosta State University — Plasma etching and cleaning is very common in the electronics fields. Since the 1970s, the use of etching has become standard in the development of substrates for microelectronics. Recently a number of commercial plasma etching systems have been introduced to the market. However, the systems are not commonly used in industry or in academia since there effectiveness has not be adequately verified in the literature. In this poster, we present spectroscopic measurements of the plasma produced by a commercial plasma etching system in an effort to start this verification process.

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